Amendments to the Specification:

Please replace the paragraph bridging pages 1 and 2 with the following amended paragraph:

Various types of triazole compounds have so far been reported as agents for the treatment of fungal infections. For example, triazole compounds having a tertiary hydroxy group are described in Japanese Patent Application Publication No. Hei 8-333350, Japanese Patent Application Publication No. Hei 11-80135, Japanese Patent Application Publication No. Hei 10-279567, and Japanese Patent Application Publication No. 2001-342187. In Japanese Patent Application Publication No. Sho 62-14766, 2-(2,4-difluorophenyl)-1,3-bis(1H-1,2,4-triazol-1-yl)-2-propanol (fluconazole) is described. In Japanese Patent Application Publication No. Hei 8-53426, 3-[4-(4-cyanophenyl)thiazol-2-yl]-2-(2,4-difluorophenyl)-1-(1H-1,2,4-triazol-1-yl)-2-butanol (ravuconazole) is described. In WO 99/45008, 2-(2,5-difluorophenyl)-3-[4-(4-cyanophenyl)thiazol-2-yl]-1-(1H-1,2,4-triazol-1-yl)-2-butanol (R00094815) is described. In Japanese Patent No. 2625584, 2-(2,4-difluorophenyl)-3-(5-fluoro-4-pyrimidinyl)-1-(1H-1,2,4-triazol-1-yl)-2-butanol (voriconazole) is described. In Japanese Patent Application Publication No. Hei

9-183769, 1-[(1R,2R)-2-(2,4-difluorophenyl)-2-hydroxy-1-methyl-3-(1H-1,2,4-triazol-1-yl)propyl]-3-[4-(1H-1-tetrazolyl)phenyl]-2-imidazolidinone (TAK-456) is described. In Japanese Patent Application Publication No. Hei 11-240871, 2-(2,4-difluorophenyl)-1-(ethylsulfonyl)-1,1-difluoro-3-(1H-1,2,4-triazol-1-yl)-2-propanol (SS750) is described. In WO 98/31675, (2R,3R)-2-(2,4-difluorophenyl)-3-[4-[4-[3-oxo-2-(4-trifluoromethoxybenzyl)-2H-1,2,4-triazol-4-yl]phenyl]-1-piperazinyl]-1-(1H-1,2,4-triazol-1-yl)-2-butanol (Syn-2869) is described. In WO97/05130, 7-chloro-3-[(1R,2R)-2-(2,4-difluorophenyl)-2-hydroxy-1-methyl-3-(1H-1,2,4-triazol-1-yl)propyl]quinazolin-4(3H)-one (UR-9825) is described. Analogous triazole compounds are also described in Japanese Patent No. 3050982, WO 95/25107, WO 00/27852, WO 01/66551, and WO 01/79196.

Please replace the paragraph beginning on line 26 of page 97 with the following amended paragraph:

For example, compounds wherein X represents general formula (III) can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 8-333350, Japanese Patent Application Publication Number Hei 10-279567,

Japanese Patent Application Publication Number Hei 11-80135 and Japanese Patent Application Publication Number 2001-342187.

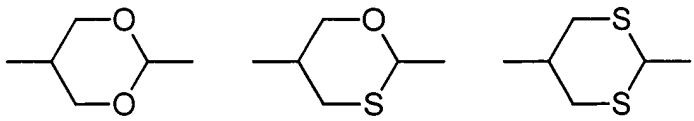
Please replace the paragraph bridging pages 97 and 98 with the following amended paragraph:

Particularly, compounds wherein X represents general formula (III), Ar^2 represents a phenyl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ or a monocyclic heteroaryl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ, E represents a group of formula $-S(O)_{n1}-$ (wherein, n1 is an integer from 0 to 2), R^4 represents a C_1-C_4 alkyl group, R^5 represents a hydrogen atom or a C_1-C_4 alkyl group, and G represents a group of formula (Ga') can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 8-333350.

Please replace the two full paragraphs beginning on line 8 of page 98 with the following amended paragraphs:

Compounds wherein X represents general formula (III), E represents a methylene group, A^1 represents a group selected from

the group,



(B1) (B2) (B3)

and G represents a group of formula (Ga") can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 11-80135.

Compounds wherein X represents general formula (III), Ar^2 represents a naphthyl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ or a fused bicyclic heteroaryl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ, E represents a group of formula $-S(O)_{n1}-$ (wherein, n1 is an integer from 0 to 2), R^4 represents a C_1-C_6 alkyl group, R^5 represents a hydrogen atom, and G represents a group of formula (Ga') can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 10-279567.

Please replace the paragraph bridging pages 98 and 99 with the following amended paragraph:

Compounds wherein X represents general formula (III), Ar^2 represents a phenyl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ or a naphthyl group which may optionally be substituted with 1 to 5 same or different group(s) selected from the group consisting of Substituent group γ, E represents a methylene group or a sulfur atom, R^5 represents a hydrogen atom, and G represents a group of formula (Gb) can be synthesized according to the methods described in Japanese Patent Application Publication Number 2001-342187.

Please replace the first two full paragraphs beginning on line 4 of page 99 with the following amended paragraphs:

Compounds wherein X represents general formula (VI) can be synthesized according to the methods described in Japanese Patent Application Publication Number Sho 62-14766.

Compounds wherein X represents general formula (VII) can be synthesized according to the methods described in Japanese Patent

Application Publication Number Hei 8-53426.

Please replace the two paragraphs on lines 16 to 21 on page 99 with the following amended paragraphs:

Compounds wherein X represents general formula (X) can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 9-183769.

Compounds wherein X represents general formula (XI) can be synthesized according to the methods described in Japanese Patent Application Publication Number Hei 11-240871.

Please replace the paragraph bridging pages 299 and 300 with the following amended paragraph:

A mixture of 3-fluoro-4-[(1E,3E)-5-oxo-1,3-pentadienyl]benzonitrile (4.63 g, 23.0 mmol) obtained from Reference example 1-(2), (2R,3R)-2-(2,4-difluorophenyl)-3-[[1-(hydroxymethyl)-2-hydroxyethyl]thio]-1-(1H-1,2,4-triazol-1-yl)-2-butanol (described in Japanese Patent Application Publication (Kokai) No. Hei 8-333350, 8.73 g, 24.3 mmol), p-toluenesulfonic acid monohydrate (5.07 g, 26.7 mmol) and anhydrous

tetrahydrofuran (200 ml) was allowed to stand at ambient temperature for 30 minutes. At the end of this time, the reaction mixture was concentrated using a rotary evaporator and dried *in vacuo*. The resulting residue was dissolved in anhydrous tetrahydrofuran (150 ml) and the resulting mixture was then evaporated to dryness *in vacuo* using a rotary evaporator. This procedure was repeated twice more. A solution of the resulting residue in anhydrous tetrahydrofuran (150 ml) was poured into a saturated aqueous sodium hydrogen carbonate solution with stirring. The product was then extracted with ethyl acetate and the organic layer was washed with aqueous sodium chloride solution, dried over anhydrous magnesium sulfate and then concentrated under reduced pressure. The residual oil was purified by chromatography on a silica gel (500 g; eluent, ethyl acetate : hexane = 2: 1), to give the title target compound (9.35 g, yield 74%) as a pale yellow amorphous solid.

NMR spectrum (400 MHz, $CDCl_3$) δ ppm: 1.19 (3H, d, J=7 Hz), 3.33 (1H, q, J=7 Hz), 3.40 (1H, tt, J=11, 5 Hz), 3.62 (1H, t, J=11 Hz), 3.64 (1H, t, J=11 Hz), 4.30 (1H, ddd, J=11, 5, 2 Hz), 4.43 (1H, ddd, J=11, 5, 2 Hz), 4.83 (1H, d, J=14 Hz), 5.01 (1H, s), 5.03 (1H, d, J=14 Hz), 5.07 (1H, d, J=4 Hz), 5.90 (1H, dd, J=15, 4 Hz), 6.62 (1H, dd, J=15, 11 Hz), 6.7-6.8 (2H, m), 6.73

(1H, d, J=16 Hz), 6.95 (1H, dd, J=16, 11 Hz), 7.3-7.4 (1H, m), 7.34 (1H, d, J=9 Hz), 7.40 (1H, d, J=8 Hz), 7.58 (1H, t, J=8 Hz), 7.79 (2H, s)

IR spectrum ν max (KBr) cm^{-1}: 2232, 1616, 1499, 1418, 1140

Mass spectrum m/z (FAB): 543 (M^++1)

Specific rotation $[\alpha]_D^{25}$ -76.6° (c=1.00, $CHCl_3$)